

Abstract Submitted
for the GEC10 Meeting of
The American Physical Society

What We Learned and Used in the first Inductively Coupled Plasma, ICP, for Plasma Processing and in later development JOHN H. KELLER, K2 Keller Consulting, LLC — The first ICP for Plasma Processing, also called Radio Frequency Induction, RFI, were developed at IBM, East Fishkill, NY, USA. These were extremely efficient at producing high density plasma. This paper will discuss: 1) How to drive the antenna to get high plasma density with low plasma voltage and low capacitively coupled plasma, CCP, losses, 2) Low matching losses, 3) Optimum way (presets) to start an ICP, 4) Frequency effects and 5) Achieving high plasma stability.

John H. Keller

Date submitted: 02 Jun 2010

Electronic form version 1.4